

**Form PTO-1449** (modified)  
List of Patents and Publications  
For Applicant's Information  
Disclosure Statement  
(Use several sheets if necessary)

ATTY. DKT. NO. 5589-00501

APPLICANT: Xu et al.

FILING DATE: May 10, 2001

SERIAL NO. 09/854,177

GROUP: 2812

**U.S. PATENT DOCUMENTS**

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>JW</i>	A1	4,599,558	7/1986	Castellano, Jr. et al.			
	A2	4,812,756	3/1989	Curtis et al.			
	A3	5,485,091	1/1996	Verkuil			
	A4	5,594,247	1/1997	Verkuil et al.			
	A5	5,644,223	7/1997	Verkuil			
	A6	5,650,731	7/1997	Fung et al.			
	A7	5,661,408	8/1997	Kamieniecki et al.			
	A8	5,742,658	4/1998	Tiffin et al.			
	A9	5,767,693	6/1998	Verkuil			
	A10	5,852,232	12/1998	Samsavar et al.			
	A11	5,866,806	2/1999	Samsavar et al.			
	A12	5,948,972	9/1999	Samsavar et al.			
	A13	5,955,661	9/1999	Samsavar et al.			
	A14	6,011,404	1/2000	Ma et al.			
	A15	6,191,605	2/2001	Miller et al.			
	A16	6,202,029	3/2001	Verkuil et al.			
<i>JW</i>	A17	6,267,005	7/2001	Samsavar et al.			

**FOREIGN PATENT DOCUMENTS**

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES/NO

**OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)**

<i>JW</i>	A18	Miller, "A New Approach for Measuring Oxide Thickness," Semiconductor International, July 1995, pp. 147-148.					

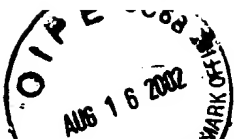
EXAMINER:

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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the patent owner.

Information Disclosure Statement--PTO 1449 (modified)



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<i>JV</i>	B1	3,495,269	2/1970	Mutschler et al.			
	B2	3,496,352	2/1970	Jugle			
	B3	4,734,721	3/1988	Boyer et al.			
	B4	5,834,941	11/1998	Verkuil			
	B5	6,060,709	5/2000	Verkuil et al.			
	B6	6,072,320	6/2000	Verkuil			
	B7	6,091,257	7/2000	Verkuil et al.			
	B8	6,097,196	8/2000	Verkuil et al.			
	B9	6,104,206	8/2000	Verkuil			
	B10	6,121,783	9/2000	Horner et al.			
	B11	6,201,999	3/2001	Jevtic			
<i>JV</i>	B12	6,224,638	5/2001	Jevtic et al.			

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EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES/NO
<i>JV</i>	B13	<i>J</i> 98/57358	12/1998	WO			

**OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)**

<i>JV</i>	B14	Numerical Recipes in C, The Art of Scientific Computing, 2nd Ed., © Cambridge University Press 1988, 1992, p. 683.
	B15	Weinberg, "Tunneling of Electrons from Si into Thermally Grown SiO <sub>2</sub> ," Solid-State Electronics, 1977, Vol. 20, pp. 11-18.
	B16	Verkuil, "Rapid Contactless Method for Measuring Fixed Oxide Charge Associated with Silicon Processing," IBM Technical Disclosure Bulletin, Vol. 24, No. 6, 1981, pp. 3048-3053.
	B17	"Contactless Photovoltage vs. Bias Method for Determining Flat-Band Voltage," IBM Technical Disclosure Bulletin, Vol. 32, Vol. 9A, 1990, pp. 14-17.
<i>JV</i>	B18	"Contactless Electrical Equivalent Oxide Thickness Measurement," IBM Technical Disclosure Bulletin, Vol. 29, No. 10, 1987, pp. 4622-4623.

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